

REMARKS

Claims 1-26 and 28-32 are pending of which claims 1-16 (drawn to the apparatus) are withdrawn and claims 17-26 and 28-32 are under examination; no new claims have been presented. Independent claim 17 and dependent claim 26 have been amended herein.

The examiner is authorized to cancel the withdrawn claims in the event the claims under examination are found allowable.

This paper is in response to the FINAL Office action dated August 22, 2007 in which independent claim 17 and claims 21-26 were rejected under 35 U.S.C. 103(a) as being unpatentable over Japan '834 in view of either Fujimoto (U.S. 5,939,139) or Taiwan '340, claims 18-20 and 28 were rejected under 35 U.S.C. 103(a) as being unpatentable over Japan '834 in view of Fujimoto or Taiwan '340 further in view of Martin (US 5,766,496) or Ellerson (U.S. 5,252,179), and, lastly, claims 27-32 were rejected over the Japan '834, Fujimoto or Taiwan '340 and Martin or Ellerson further in view of Ni (U.S. 6,200,387).

It is submitted that no new issues are raised and that entry of this amendment and a reconsideration is appropriate view of the discussion below.

Independent method claim 17 has been amended to more fully define the invention including the substantial absence of relative movement between the integrated circuit and the deposited liquid encapsulant-removing agent during the heating of the deposited liquid encapsulant-removing agent by the heated gas flow. Dependent claim 26 has been amended to address a minor syntax issue.

It is submitted that the applied references do not anticipate nor render the pending claims obvious as follows:

Japan '834, teaches the "dropping" of a varnish solvent onto a varnished printed circuit board while the printed circuit board is under a ventilation hood; there is no explicit or inherent teaching of a shape-sustaining and substantially position-maintaining deposit on the selected surface area. Since the liquid being deposited in Japan '834 is a varnish solvent, the higher probability is that the solvent will not constitute a shape-sustaining and substantially position-maintaining deposit.

Fujimoto teaches removal of accumulated spin-coated resin from the peripheral edge of a wafer W in a spin coat machine by use of a solvent delivered by a first nozzle 21 while a second nozzle 22 directs a gas flow to blow the solvent/resin mix off the edge of the spinning wafer W. In Fujimoto, the solvent cannot possible form a shape-sustaining and substantially position-maintaining deposit in view of the spinning wafer W. It is noted

that in FIG. 7 of Fujimoto, the gas jet is always initiated (step S5) after initiation of wafer rotation (step S3) and terminated (step S8) before termination of wafer rotation (step S10). Thus, Fujimoto cannot teach the absence of substantial relative movement between the gas flow and the spinning wafer W. It is the applicant's view that the explicit disclosure of relative movement between the spinning wafer W and the gas flow militates against the use of a substantially stationary gas flow in Japan '834.

Taiwan '340 is silent as to any type of heated gas flow and teaches, alternatively, the heating of the integrated circuit package or the heating of the etching liquid; Taiwan '340 is deficient in not disclosing a heated gas flow.

The claimed shape-sustaining and substantially position-maintaining deposit is not explicitly or implicitly shown in Japan '834 and Fujimoto's teaching of "vigorous" film removal at Col. 5, Lines 34-37, if hypothetically combined with Japan '834, is clearly in a direction opposite to that of claim 17 and its dependent claims.

In view of the above, it is submitted that independent claim 17 and its dependent claims are in condition for allowance and an indication thereof is respectfully requested.

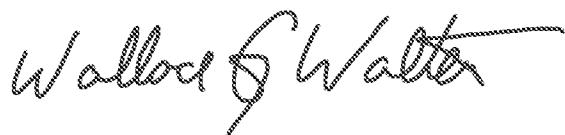
Date: Sept 21, 2007

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Atty Docket: SE-2021-TD

Respectfully submitted,



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